

Results of 2024: Key Elements for Future Metrology at IMT

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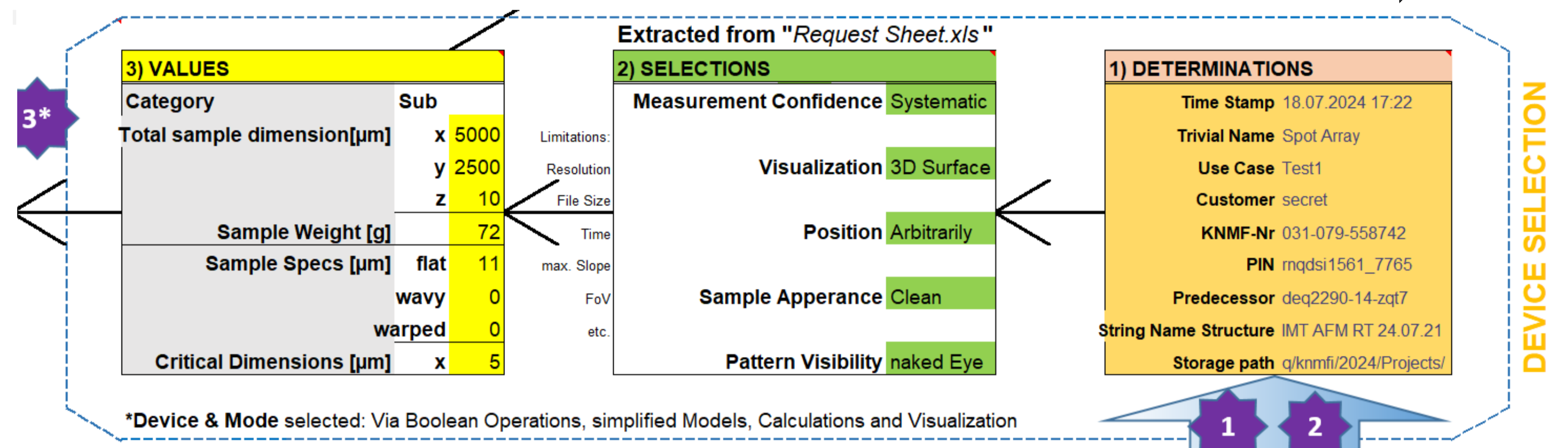
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1) Standardized Flow
See MSE Day Poster
Richard Thelen

2) Guided Dialogue (.xls Model)
to convert research question
into metrology process flow



partially interactive



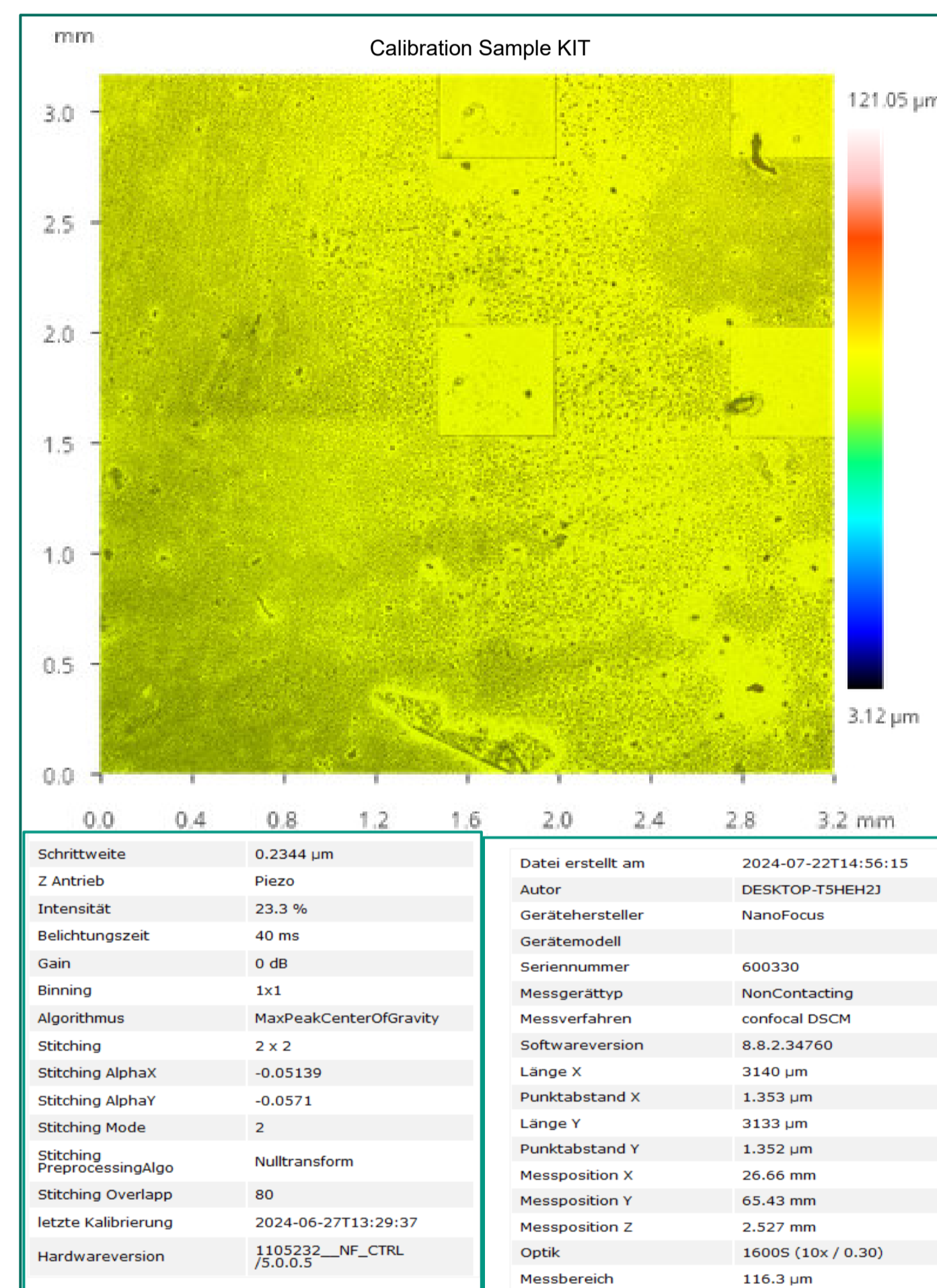
3) Python Script
to extract and convert
metadata for ELN use

To	To	From	To	To	From	
ELN	EXCEL	Python	Mountains	Python	Device	
	Standardized Script		Individual			
	JSON	XLS	CSV			
			spm	spm	spm	AFM
			.obd	.xml	.obdx	VSI
			.fits	.html	.fits	CSM
					.czi	XYZ
						SEM/OM
	tbd					

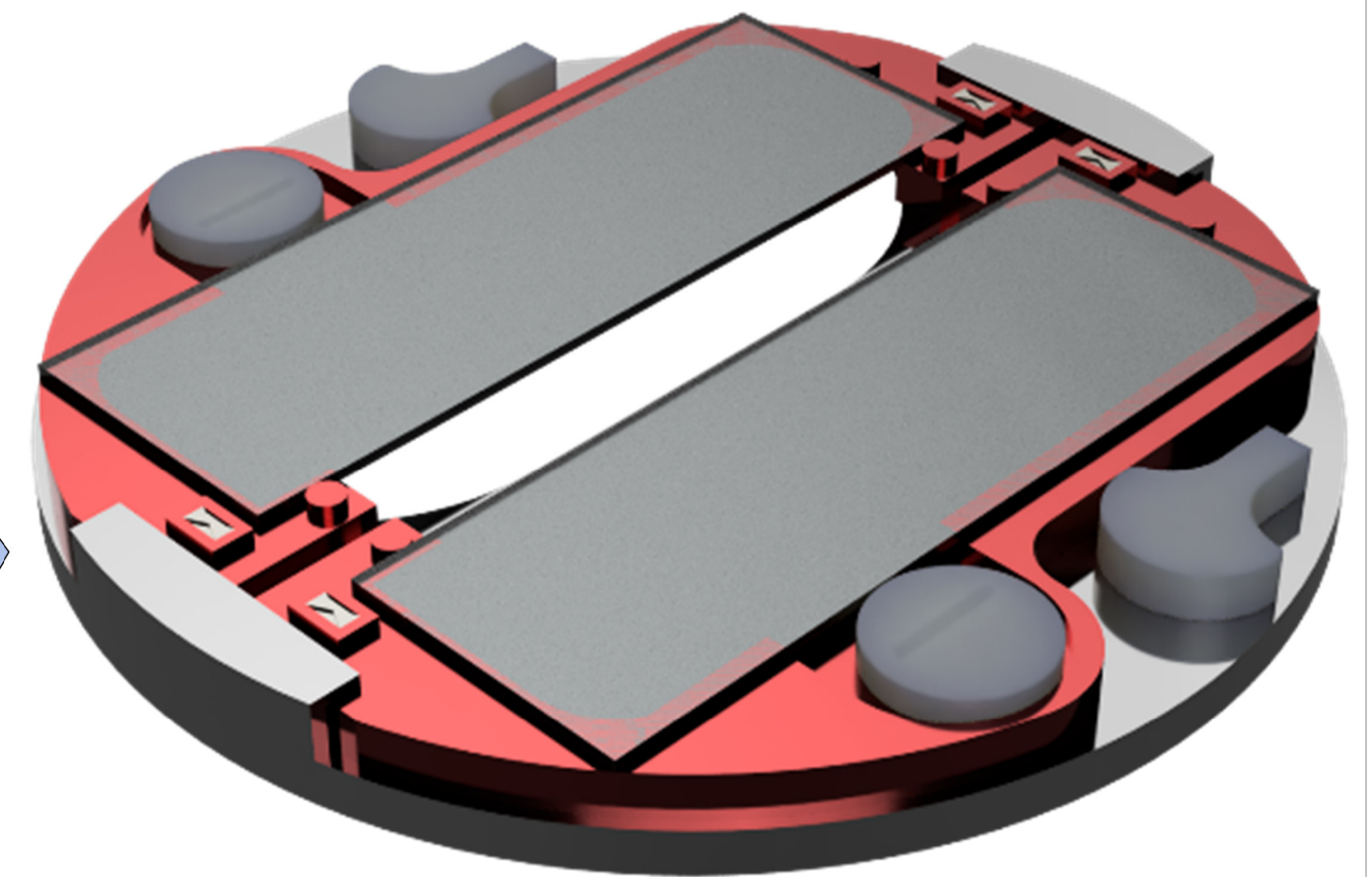
tbtd Coding: R. Kietz

METADATA CONVERSION

4) Standardized + scaled
Preview → picture search.
NO search by key words



5) 3D Printed Carrier
compensates theta,
tip and tilt, manually



6) 3D Vector Alignment
See MSE Day Poster
Max Kabbe

Future MDMC Metrology Topics at IMT

Sample Navigation System

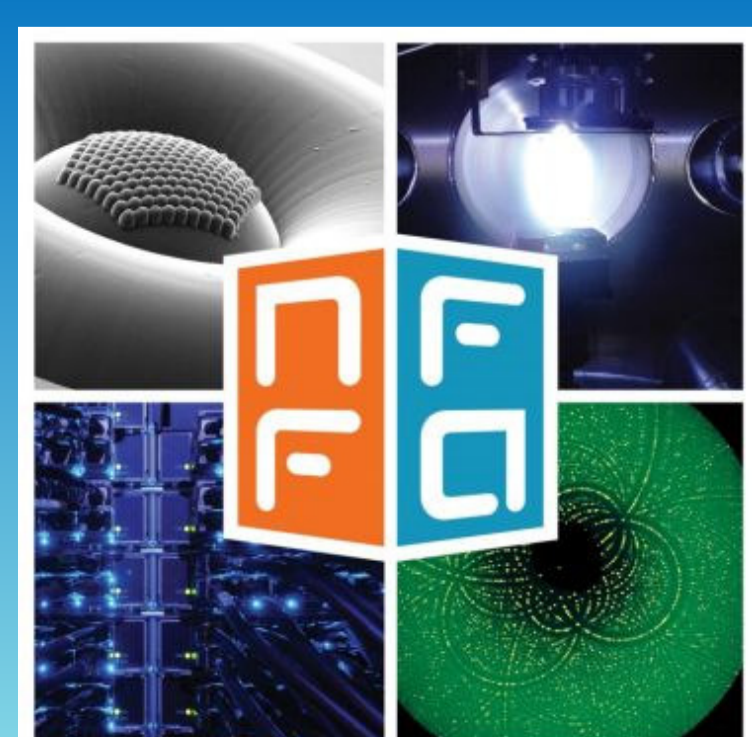
Human-machine communication and optimized algorithms for quality improvement in high-precision measurement processes using animated navigation to define measurement points on a sample surface

The devices will perform with best possible compensation using integrated machine learning. The necessary multi-parameter optimization will be supported by AI to determine the best path and convert it into a machine-readable form. This concerns the design of the mechanical interface and the actuators as well as the determination of the method for the best possible compensation.

Motorized Carrier

Universal and compact carrier with integrated mechanics for converting position data into correction values in the event of position deviation over several degrees of freedom.

The device-independent carrier with active compensation of position deviations offers a universal solution to the problem of lacking alignment options. Without requiring access to the often proprietary manufacturer software or further investment in improving the individual device stages for additional degrees of freedom DoF.



Collaboration
Opportunities



Institute of Microstructure Technology

